COMBINATION SYSTEM SERIES

ELECTRON BEAM EVAPORATION ION BEAM ASSISTED DEPOSITION

STANDARD FEATURES:

Electro-Polished Stainless Steel Chamber (D-Shaped Box)

4" Diameter View Port on Front Door with Manual Shutter

Single / Multi pocket E-Beam Source with Water Cooled Crucible (4cc up to 75cc) with Individual Shutter

High Voltage Power Supply (3kW to 15 kW) with X-Y Sweep Controller

Turbo Molecular Vacuum Pumping System with Matching Dual Stage Rotary Vane Pump

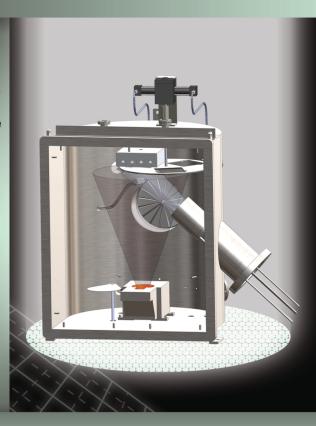
Quartz Crystal Thickness Sensor with Deposition Controller

Full Range Vacuum Gauge with Digital Display & Readout

Ion Beam Assisted Deposition with Divergent Beam Ion Source & Power Supply

115mm Substrate Stage

PLC Controlled System



Water Chiller

Load Locked System with Sample Transfer Adaptability

Multi-Axis Substrate Stage Rotation

Quartz Lamp Heater (from 300° C up to 800° C)

Planetary Substrate Stage

Motorized Shutter Assembly

PC Controlled System

Water Cooled Substrate Stage

Adjustable Size & Height Available for Substrate Stage

SQC 310 Film Thickness Monitor & Deposition Controller

In-Situ Mask Change

Large Capacity Crucible & Power Supply

Dry Scroll Pump

Cryo Pumping System

Cold Cathode or Hot Cathode Ionization Gauge Additional Spare Flanges for Future Upgrades



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